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Aq. colloidal dispersions used in mfg. non slip floor waxes - contain silica, acid and stabiliser

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Number of Countries: 012 Number of Patents: 015

Patent Family:

Patent No	Kind	Date	Applicat No	Kind	Date	Week	
GB 2229432	A	19900926	GB 906122	A	19900319	199039	B
DE 4006392	A	19900927	DE 4006392	A	19900301	199040	
AU 9052010	A	19900927				199046	
FR 2644768	A	19900928	FR 903557	A	19900320	199046	
CA 2012719	A	19900921				199049	
JP 3060420	A	19910315	JP 9068568	A	19900320	199117	
BR 9001302	A	19910402				199118	
CN 1045754	A	19901003				199124	
BE 1002854	A	19910702	BE 90319	A	19900321	199135	
GB 2229432	B	19920923	GB 906122	A	19900319	199239	
US 5246624	A	19930921	US 89326890	A	19890321	199339	
			US 92829609	A	19920130		
IT 1239546	B	19931105	IT 9019748	A	19900321	199411	
CA 2012719	C	19990608	CA 2012719	A	19900321	199941	
JP 2949633	B2	19990920	JP 9068568	A	19900320	199944	
KR 148692	B1	19980817	KR 903705	A	19900320	200022	

Priority Applications (No Type Date): US 89326890 A 19890321; US 92829609 A 19920130

Patent Details:

Patent No	Kind	Lan	Pg	Main IPC	Filing Notes
GB 2229432	A		20		
US 5246624	A		5	B01J-013/00	Cont of application US 89326890
CA 2012719	C	E		B01F-017/54	
JP 2949633	B2		5	C01B-033/141	Previous Publ. patent JP 3060420
KR 148692	B1			C01B-033/14	
GB 2229432	B			C01B-033/14	
IT 1239546	B			C01B-000/00	

Abstract (Basic): GB 2229432 A

Aq. dispersion (I) contains 40 wt.% at least fumed SiO₂, 0.0025-0.05% acid (w.r.t. SiO₂ wt.) plus stabiliser (II) to maintain a 7-12 pH. Acid is e.g. HCl, H₂SO₄, HAc, H₃PO₃ etc. (II) is e.g. KOH, NH₄OH, triethylamine etc. SiO₂ component pref. has a 10-75 sq.m/g surface area.

USE/ADVANTAGE - (I) is used in mfg. non slip floor waxes, foamed rubber lattices, paper coatings, optical fibres, quartz glassware and in polishing and fractionising. (I) are easily filtered and can pass 10 micron pore size filters. (I) are non dilatant, have viscosities below 250 cps. and do not gel for at least one day.

Dwg.0/0

Abstract (Equivalent): GB 2229432 B

A colloidal dispersion comprising at least 40% by weight fumed silica, acid in an amount between 0.0025% and 0.5% of the amount by

weight of the fumed silica, an amount by weight of stabiliser which will raise the pH of the dispersion to between 7.0 and 12.0, dispersed in water.

(Dwg.0/0)

Abstract (Equivalent): US 5246624 A

A high solids colloidal dispersion of fumed silica is obtd. by dispersing an amount of silica equal to at least 40% solids into water acidified with 0.0025-0.5% of organic or mineral acid. After mixing under high shear conditions a pH raising stabiliser is added to adjust the pH to 7-12. The resulting dispersion will not gel for at least one day and has a viscosity below 1000 centipoise.

ADVANTAGE - The material is suitable for use in non-slip floor coating, paper coatings, foamed rubber latices thermal insulation etc.

Dwg.0/0

Title Terms: AQUEOUS; COLLOID; DISPERSE; MANUFACTURE; NON; SLIP; FLOOR; WAX ; CONTAIN; SILICA; ACID; STABILISED

Derwent Class: A60; E36; G02; L01

International Patent Class (Main): B01F-017/54; B01J-013/00; C01B-000/00; C01B-033/14; C01B-033/141

International Patent Class (Additional): C09K-003/14; D06M-011/79; D06M-013/325; D21H-019/38

File Segment: CPI

Manual Codes (CPI/A-N): A12-S04A; E10-B04D; E10-C04J; E31-B03D; E31-F05; E31-K05A; E31-P03; E32-A04; E33-A03; G02-A05C; G02-C; G04-B; G04-B04; L01-F03M; L02-F02

Plasdoc Codes (KS): 0009 0231 2499 2536

Polymer Fragment Codes (PF):

001 014 032 04- 472 491

Chemical Fragment Codes (M3):

01 C017 C100 C101 C730 C800 C801 C804 C805 C806 C807 M411 M782 M903
M904 M910 Q130 Q324 Q332 Q452 R024 R01704-M
02 C101 C108 C316 C540 C730 C800 C801 C802 C804 C805 M411 M782 M903
M904 M910 Q130 Q324 Q332 Q452 R024 R01714-M
03 C101 C108 C307 C510 C730 C800 C801 C802 C804 C807 M411 M782 M903
M904 M910 Q130 Q324 Q332 Q452 R024 R01724-M
04 B115 B701 B713 B720 B815 B831 C101 C108 C800 C802 C804 C805 C807
M411 M782 M903 M904 M910 Q130 Q324 Q332 Q452 R024 R01711-M
05 J0 J011 J1 J171 M210 M211 M262 M281 M320 M416 M620 M782 M903 M904
M910 Q130 Q324 Q332 Q452 R024 R00247-M
06 H7 H721 J0 J012 J1 J172 M280 M312 M321 M332 M342 M382 M391 M416 M782
M903 M904 M910 Q130 Q324 Q332 Q452 R024 R00901-M
07 A103 A111 A119 A940 C101 C108 C500 C550 C730 C801 C802 C804 C805
C807 M411 M782 M903 M904 M910 Q130 Q324 Q332 Q452 Q620 R024 R01512-M
R01513-M R01514-M R01534-M
08 H1 H103 H181 M210 M212 M273 M283 M320 M416 M620 M782 M903 M904 M910
Q130 Q324 Q332 Q452 Q620 R024 R01013-M
09 H1 H103 H181 H4 H401 H481 H8 M210 M211 M273 M282 M312 M321 M332 M342
M383 M391 M416 M620 M782 M903 M904 M910 Q130 Q324 Q332 Q452 R024
R00834-M
10 B114 B702 B720 B831 C108 C800 C802 C803 C804 C805 C807 M411 M782
M903 M904 M910 Q130 Q324 Q332 Q452 R024 R01694-M

Derwent Registry Numbers: 0247-U; 0834-U; 0901-U; 1013-U; 1512-U; 1513-U; 1514-U; 1534-U; 1694-U; 1704-U; 1711-U; 1714-U; 1724-U

Specific Compound Numbers: R01704-M; R01714-M; R01724-M; R01711-M; R00247-M ; R00901-M; R01512-M; R01513-M; R01514-M; R01534-M; R01013-M; R00834-M; R01694-M

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Entgegenhaltung 6:

JP Pat.-Offenlegung Nr. 03-060420 vom 15.03.1991

Anmeldung Nr. 02-068568 vom 20.03.1990

Priorität vom 21.03.1989, US (Appln. Ser. No. 326,890)

Anmelder: Cabot Corp., US

Titel: Wäßrige kolloidale Dispersion von pyrogener Silika

(Bemerkung:

Von der Anfertigung einer Übersetzung sehen wir zunächst ab, da wir annehmen, daß Sie in der Lage sind, sich aufgrund obiger Prioritätsdaten ein für Sie lesbares Äquivalent in einer europäischen Sprache zu beschaffen. Sollte dies nicht gelingen und doch noch eine Teilübersetzung von hier erforderlich sein, dann bitten wir um Benachrichtigung.)